

LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

ABSTRACT OF THE DISCLOSURE

A programmable patterning structure for use with a lithographic

5 projection apparatus according to one embodiment of the invention includes a plurality of reflective elements A, B, C, each reflective element having two distributed Bragg reflectors 51, 52. A separation D1 between the two distributed Bragg reflectors is adjustable between a first relation, at which destructive interference between reflections from the first and second

10 distributed Bragg reflectors 51, 52 results in substantially zero reflectivity, and a second relation, in which constructive interference between reflections from the first and second distributed Bragg reflectors 51, 52 results in high reflectivity.